



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

#201VB
4/23/03

IN RE APPLICATION OF: Hiroshi IKEDA, et al.

SERIAL NO: 09/463,961

GAU: 1754

FILED: May 25, 2000

EXAMINER: Johnson, Edward M.

FOR: PROCESS AND APPARATUS FOR TREATING SEMICONDUCTOR PRODUCTION EXHAUST GASES

**REQUEST FOR EXTENSION OF TIME
UNDER 37 C.F.R. 1.136**

RECEIVED
APR 1 2003
TC 1700

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

It is hereby requested that a one month extension of time be granted to March 24, 2003 for

- filing a response to the Official Action dated: January 24, 2003
- responding to the requirements in the Notice of Allowability dated:
- filing the Formal Drawings. The Issue Fee due has been timely filed.
- responding to the Notice to File Missing Parts of Application dated:
- filing a Notice of Appeal. A timely response to the final rejection, due has been filed.
- filing an Appeal Brief. A Notice of Appeal was filed on:
- Applicant claims small entity status. See 37 CFR 1.27. Therefore, the fee amount shown below is reduced by one-half.

The required fee of \$110.00 is enclosed herewith by check and any further charges may be made against the Attorney of Record's Deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.

Respectfully Submitted,

OBLON, SPIVAK, McCLELLAND,
MAIER & NEUSTADT, P.C.

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